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Optimization on silicon detectors at CEPC

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2019.11.28

Outline

- Introduction
- Fast simulation and full simulation results
- Flavor tagging performance with different vertex geometry
- Influence of the material budget near beam pipe
- Performance of an ultra lightweight vertex layout
- Influence of SET on track and Higgs mass reconstruction

Introduction

- H \rightarrow bb, cc and gg is the core part of the CEPC Higgs program
- Vertex system with **high impact parameter resolution** is crucial

Table 6.1 Required performance of the CEPC sub-detectors for critical benchmark Higgs processes.

Physics Process	Measured Quantity	Critical Detector	Required Performance
$ZH \rightarrow \ell^+ \ell^- X$	Higgs mass, cross section	Tracker	$\Delta(1/p_T) \sim 2 \times 10^{-5}$
$H \rightarrow \mu^+ \mu^-$	$\text{BR}(H \rightarrow \mu^+ \mu^-)$		$\oplus 1 \times 10^{-3} / (p_T \sin \theta)$
$H \rightarrow b\bar{b}, c\bar{c}, gg$	$\text{BR}(H \rightarrow b\bar{b}, c\bar{c}, gg)$	Vertex	$\sigma_{r\phi} \sim 5 \oplus 10 / (p \sin^{3/2} \theta) \mu\text{m}$
$H \rightarrow q\bar{q}, VV$	$\text{BR}(H \rightarrow q\bar{q}, VV)$	ECAL, HCAL	$\sigma_E^{\text{jet}} / E \sim 3 - 4\%$
$H \rightarrow \gamma\gamma$	$\text{BR}(H \rightarrow \gamma\gamma)$	ECAL	$\sigma_E \sim 16\% / \sqrt{E} \oplus 1\% (\text{GeV})$

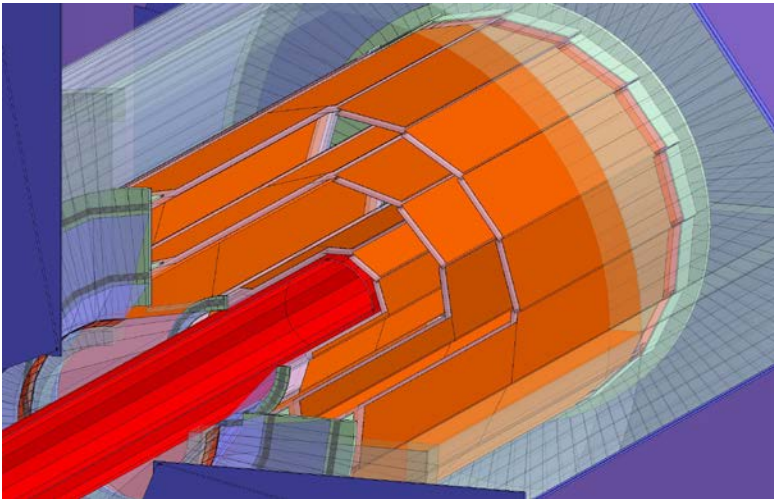
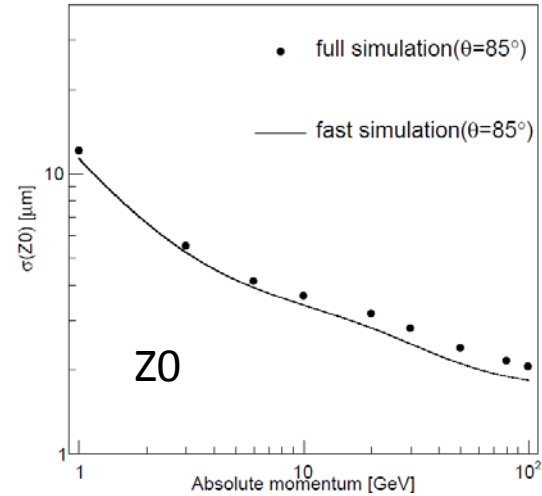
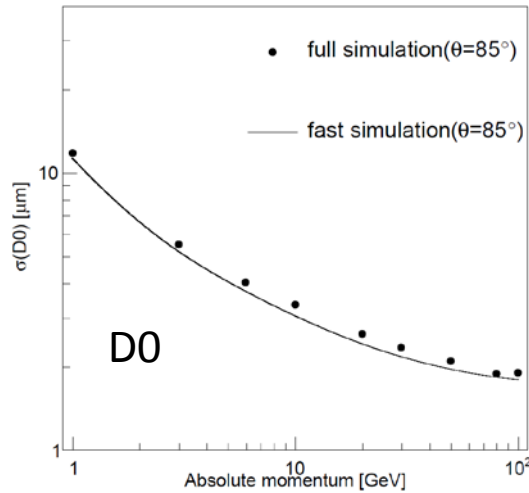


Table 1. Design parameters of the CEPC vertex system.

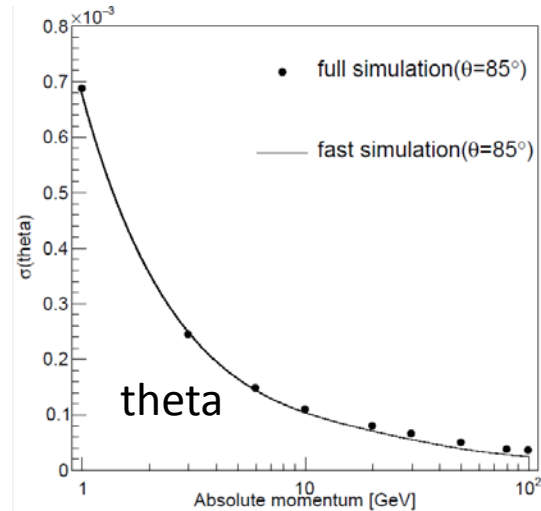
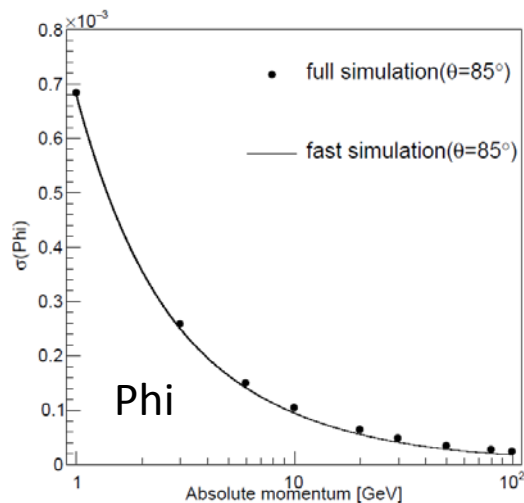
	R(mm)	Z (mm)	$\sigma(\mu\text{m})$	material budget
Layer 1	16	62.5	2.8	0.15%/X ₀
Layer 2	18	62.5	6	0.15%/X ₀
Layer 3	37	125.0	4	0.15%/X ₀
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Layer 5	58	125.0	4	0.15%/X ₀
Layer 6	60	125.0	4	0.15%/X ₀

Simulation tools

- Fast simulation: "LiC Detector Toy" (LDT) software tool
 - Full simulation: Mokka and Marlin
- consistent



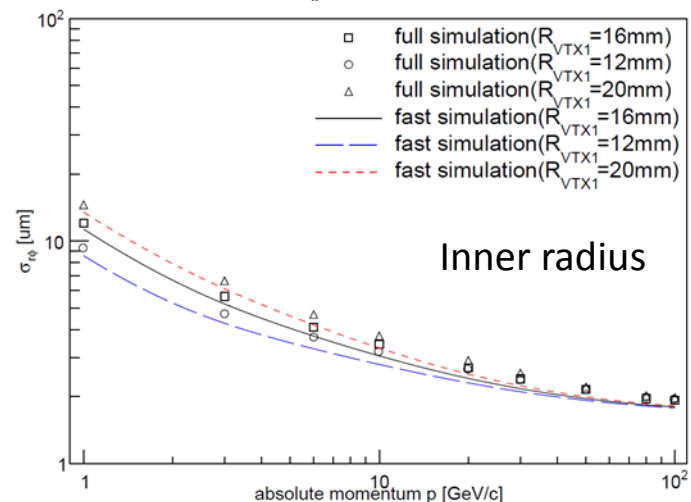
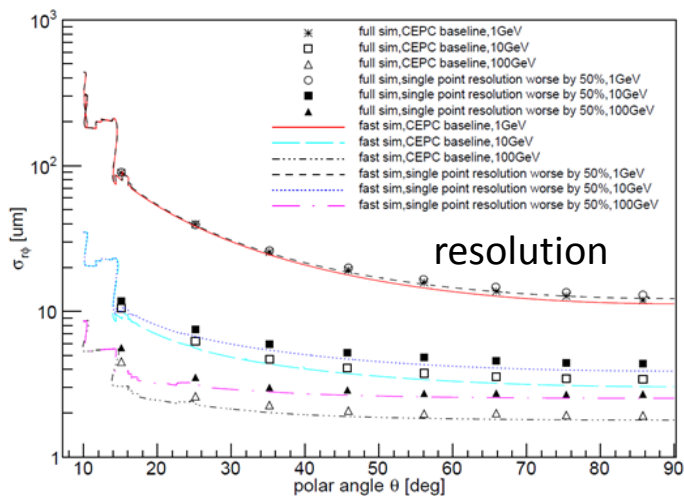
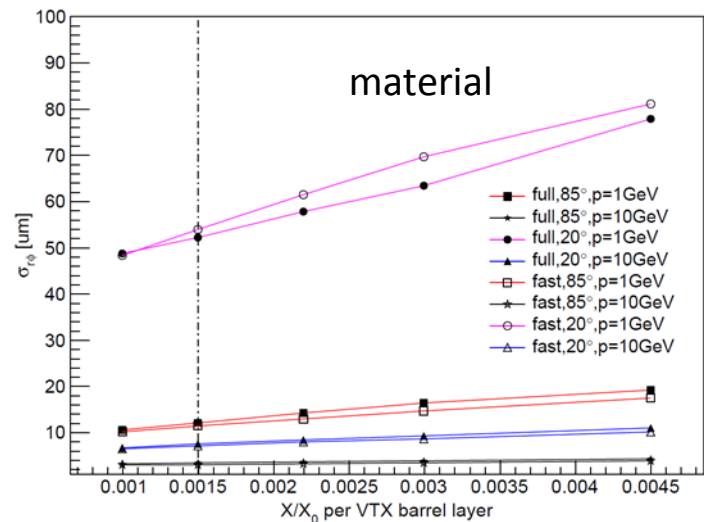
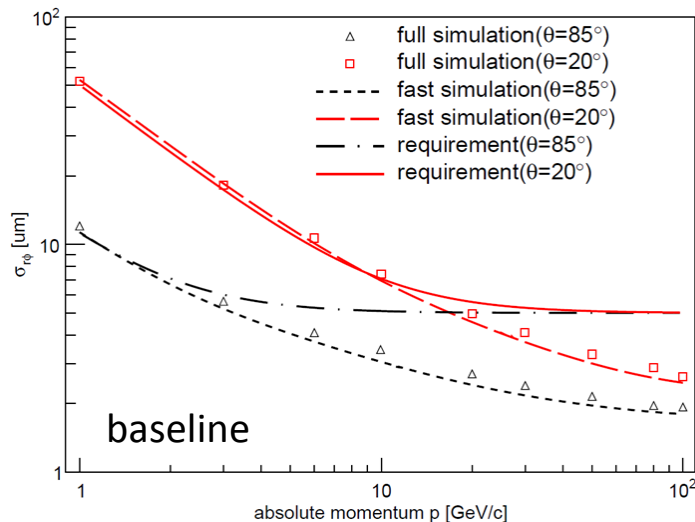
The key parameters' resolution of a helix track



Key geometry parameters

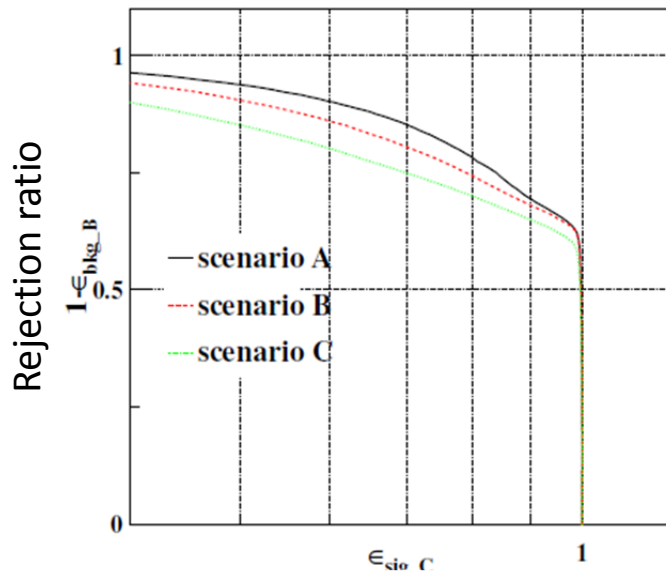
- The influence of the geometry parameters on the impact parameter resolution

□ Inner radius, Material budget, Spatial resolution

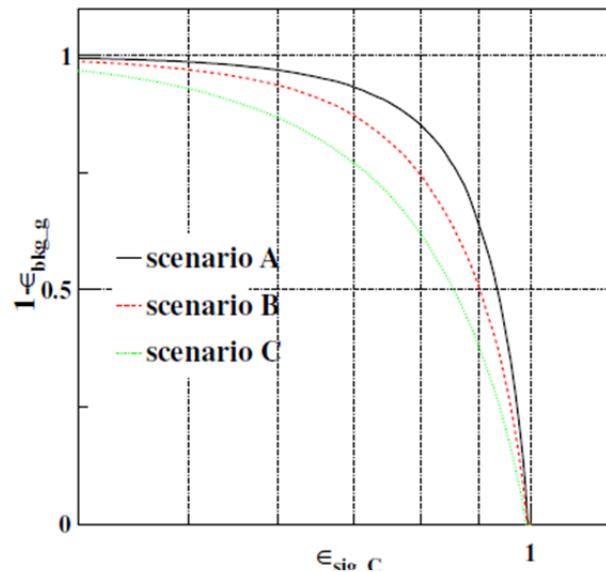


Flavor tagging performance

- Only di-jet final modes (bb, cc, gg) are considered, evaluated by ROC
 - SM bkg and other decay mode of Higgs can be effectively reduced
- Case C: upgraded ALICE ITS; Case A: half values of the baseline design



C-tagging efficiency



C-tagging efficiency

	Scenario A (Aggressive)	Scenario B (Baseline)	Scenario C (Conservative)
Material per layer/ X_0	0.075	0.15	0.3
Spatial resolution/ μm	1.4 - 3	2.8 - 6	5 - 10.7
R_{in}/mm	8	16	23

Br(H->bb, cc) measurement

- Br (H -> cc) is extremely sensitive to the vertex design
- Br (H -> bb) is less sensitive to the vertex design

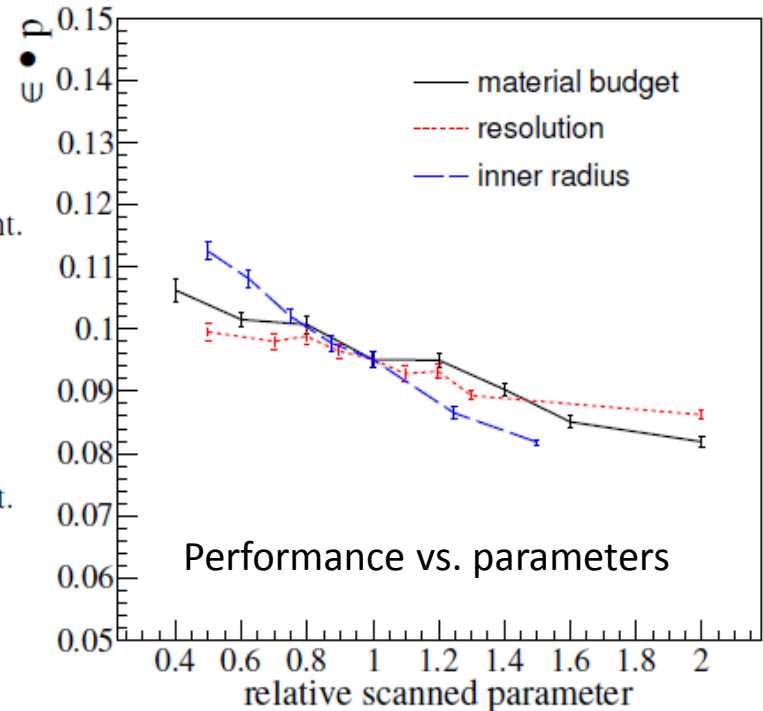
$$\frac{\delta\mu}{\mu} \propto \frac{\sqrt{S+B}}{S} = \sqrt{\frac{1}{S}} \sqrt{\frac{S+B}{S}} \propto \frac{1}{\sqrt{\epsilon \cdot p}}$$

Table 3. Maximum $\epsilon \cdot p$ value comparison for the $Br(H \rightarrow c\bar{c})$ measurement.

	Scenario A	Scenario B	Scenario C
$\epsilon \cdot p$	0.133 ± 0.002	0.095 ± 0.001	0.078 ± 0.001
	41%		-22%

Table 4. Maximum $\epsilon \cdot p$ value comparison for the $Br(H \rightarrow b\bar{b})$ measurement.

	Scenario A	Scenario B	Scenario C
$\epsilon \cdot p$	0.925 ± 0.001	0.914 ± 0.001	0.900 ± 0.001
	1%		-1.5%

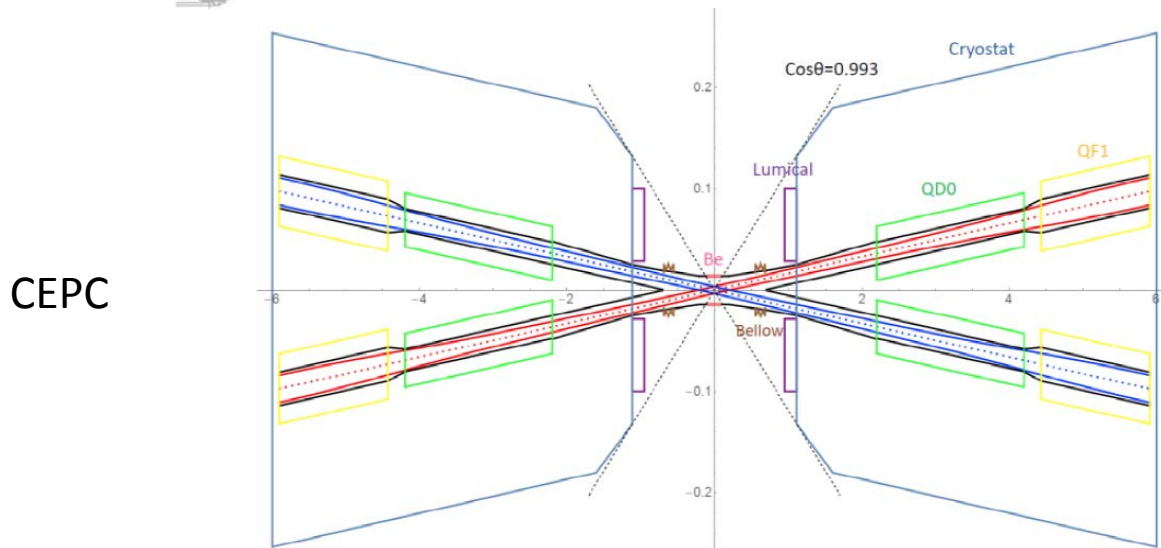
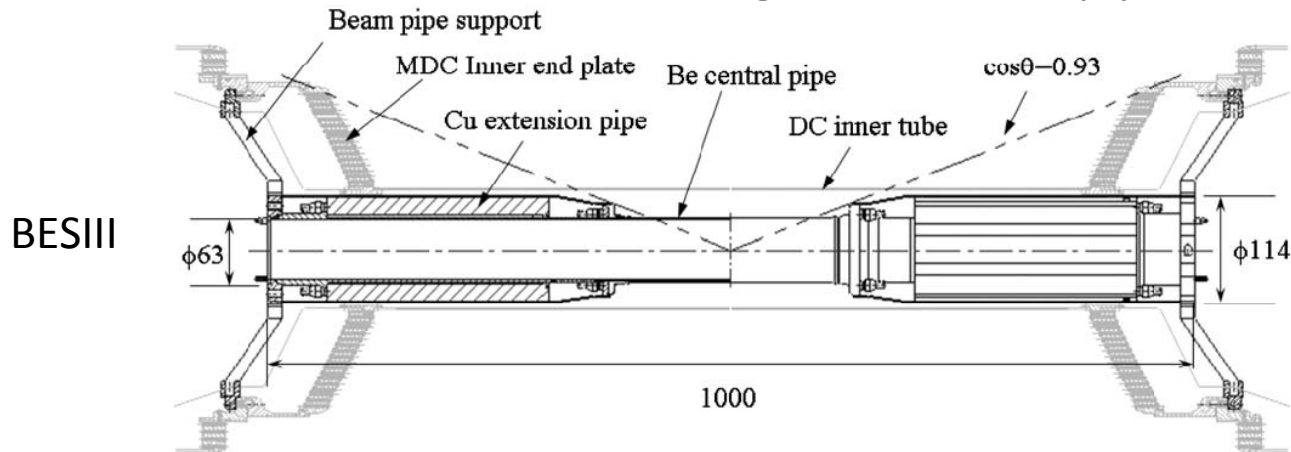


$$\epsilon \cdot p = 0.095 \left(1 - 0.14 \frac{\Delta x_{material}}{x_{material}}\right) \left(1 - 0.09 \frac{\Delta x_{resolution}}{x_{resolution}}\right) \left(1 - 0.23 \frac{\Delta x_{radius}}{x_{radius}}\right)$$

Inner radius is the most sensitive parameter

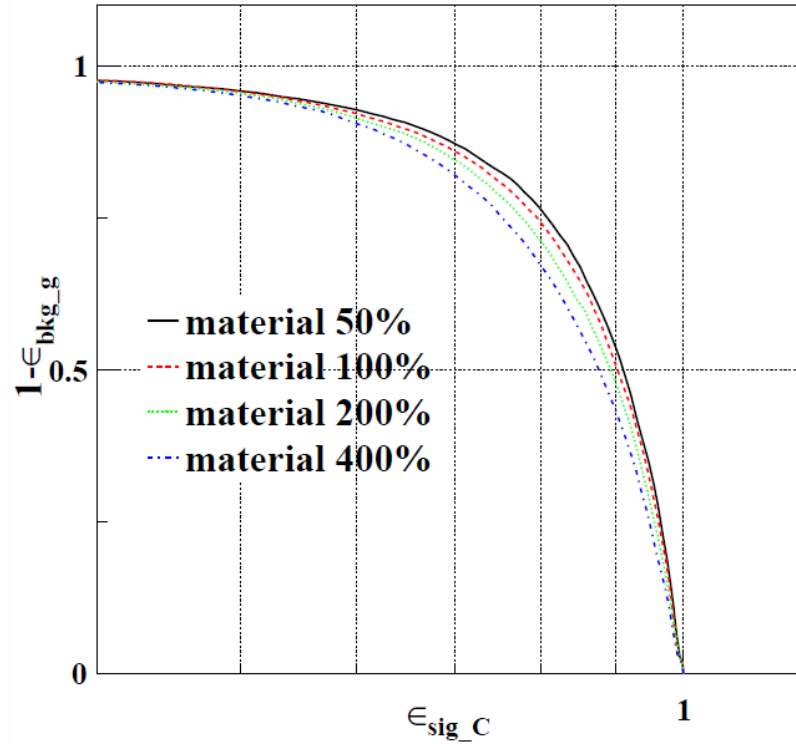
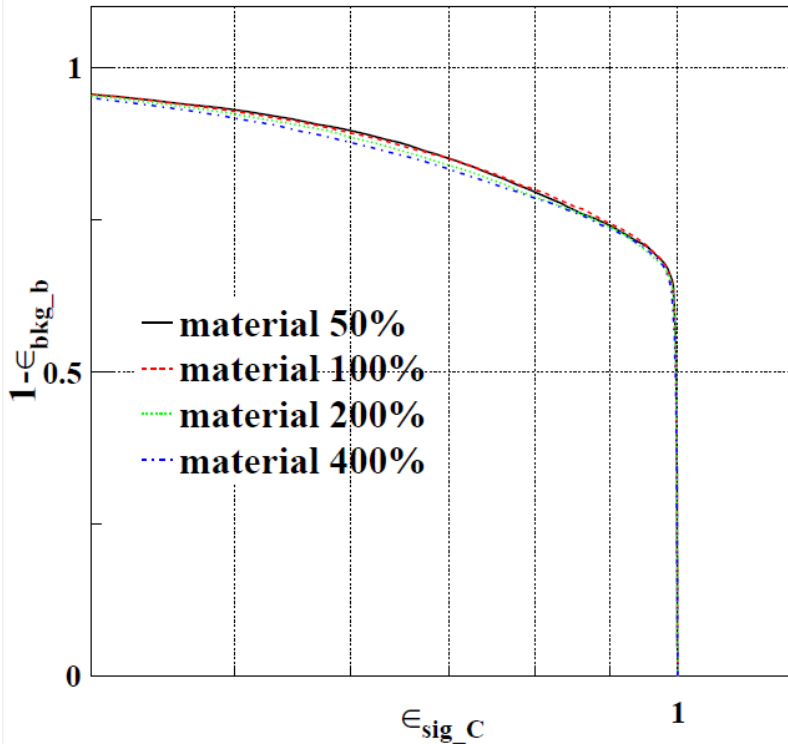
Material budget near beam pipe

- BESIII beam pipe material: $1.04\%/X_0$ (Be: 0.4%, gold: 0.44%, SMO: 0.2%)
- CEPC beam pipe material: $0.14\%/X_0$ Be, heat load more than 1000 W
- Have to increase the material budget near beam pipe due to cooling



Material budget near beam pipe

- Have to increase the material budget near beam pipe due to cooling system
- Influence is **comparable** with the material change of vertex detector



material	50%	100%	200%	400%
$\epsilon \cdot p$	0.1175	0.1145	0.1092	0.1057

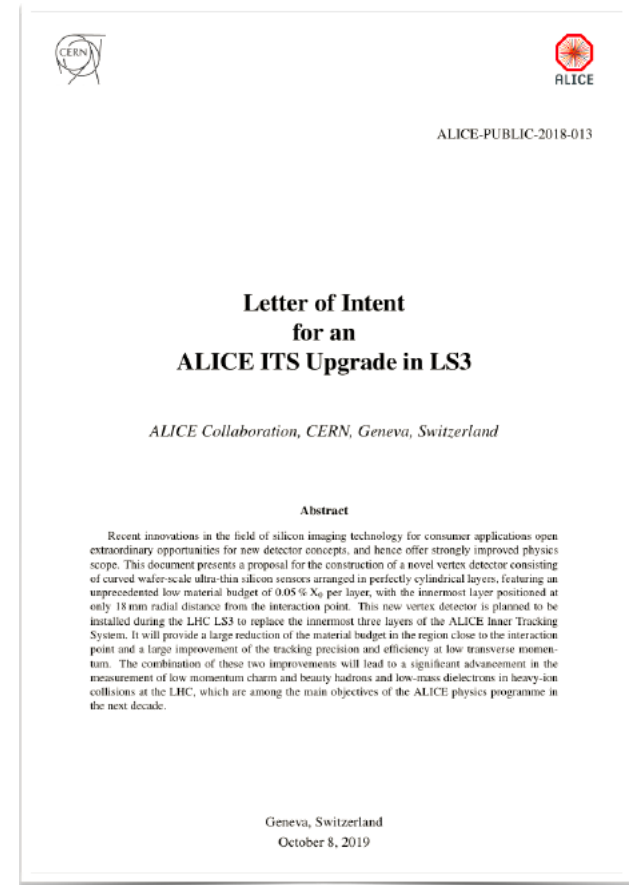
-10%

$$\epsilon \cdot p \propto 1 - 0.025 \frac{\Delta \chi_{material}}{\chi_{material}}$$

ALICE ITS3

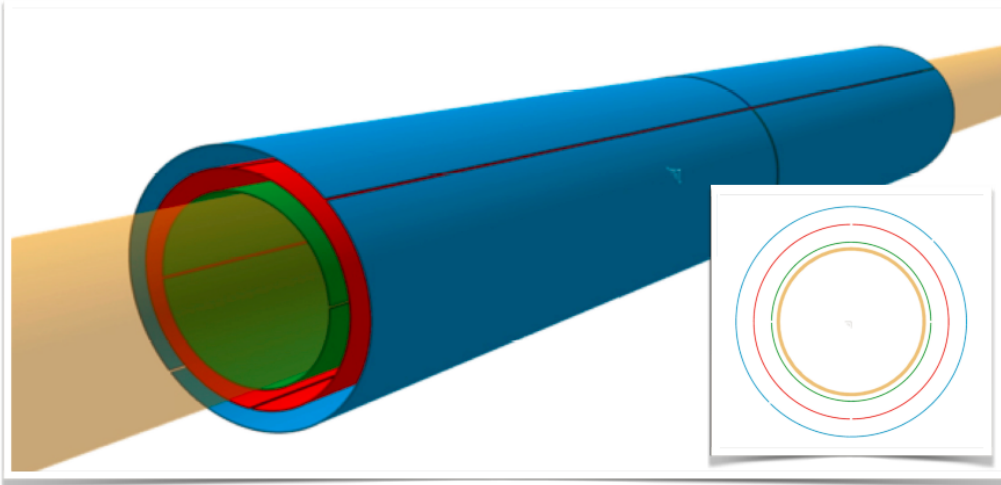
- ▶ EoI details milestones for all activities, grouped by:
 - Sensor Chip
 - Thinning and bending
 - Mechanics and cooling
 - Beam pipe
- ▶ R&D starts now
- ▶ TDR is foreseen for 2022

See: M. Mager , | ITS3 | VERTEX 2019 | 17.10.2019 |



[ALICE-PUBLIC-2018-013]

ALICE ITS3 Layout



- ▶ New beam pipe:
 - “old” radius/thickness: 18.2/0.8 mm
 - new radius/thickness: 16.0/0.5 mm

- ▶ Extremely low material budget:
 - Beam pipe thickness: 500 μm (0.14% X_0)
 - Sensor thickness: 20-40 μm (0.02-0.04% X_0)

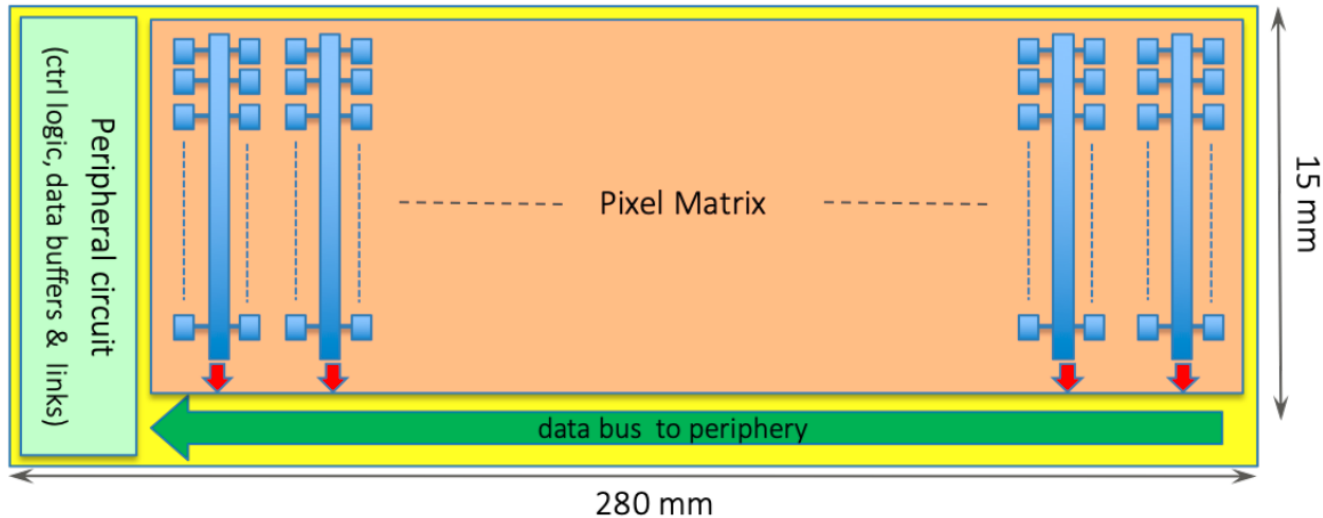
- ▶ Material homogeneously distributed:
 - essentially zero systematic error from material distribution

Beam pipe Inner/Outer Radius (mm)	16.0/16.5		
IB Layer Parameters	Layer 0	Layer 1	Layer 2
Radial position (mm)	18.0 16mm	24.0	30.0
Length (sensitive area) (mm)	300 250mm		
Pseudo-rapidity coverage	± 2.5	± 2.3	± 2.0
Active area (cm ²)	610	816	1016
Pixel sensor dimensions (mm ²)	280 x 56.5	280 x 75.5	280 x 94
Number of sensors per layer	2		
Pixel size (μm^2)	O (10 x 10)		

Similar layout with CEPC layer 1-3

Wafer-scale chip (2)

Possible architecture



- ▶ Starting from ALPIDE architecture
- ▶ Porting to 65 nm technology node
 - smaller pixels
 - larger wafers (300 mm instead of 200 mm)

- ▶ Basic building block of 15 mm height
 - to be repeated n times in vertical direction to obtain the sizes needed per layer

CEPC layer 6: L=190mm

Stitching and thinning



CMOS APS – wafer-scale integration

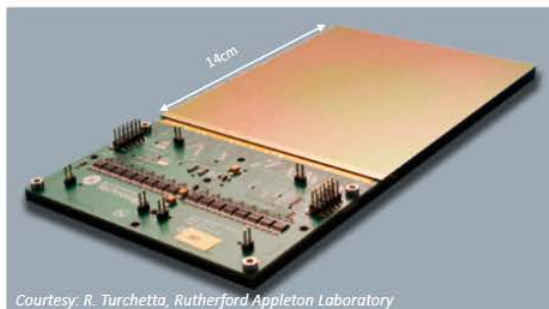
Photolithographic process defines wafer reticles size \Rightarrow Typical field of view $O(2 \times 2 \text{ cm}^2)$

Reticle is stepped across the wafers to create multiple identical images of the circuit(s)

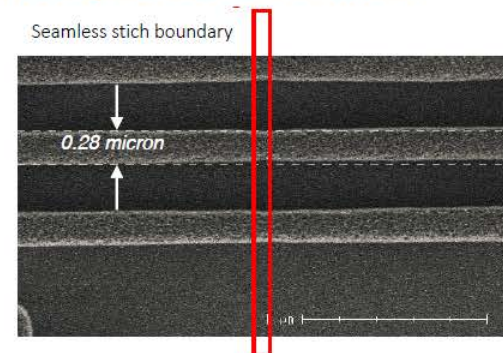
A stepping process called “stitching” allows building sensors of arbitrary size, the only limit being the size of the wafer.

- Reticle made of blocks
- Printing only individual blocks at each step with a tiny well-defined overlap

These days, stitching is widely applied in the digital imaging industry (e.g. large flat panels for medical and dental X-rays)



Courtesy: R. Turchetta, Rutherford Appleton Laboratory



Ultra-thin chip (<50 μm): flexible with good stability



Vertex layout with 6 single ultra lightweight layers — comparing with Baseline Design

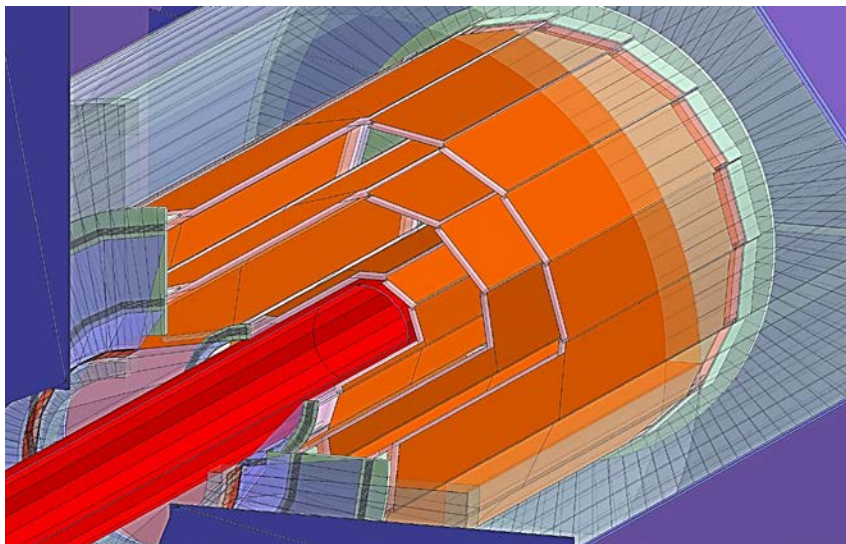
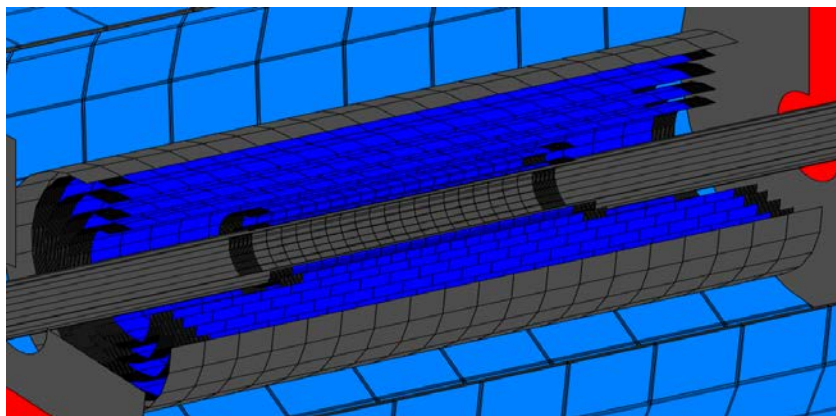
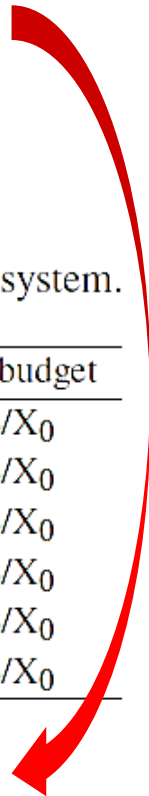


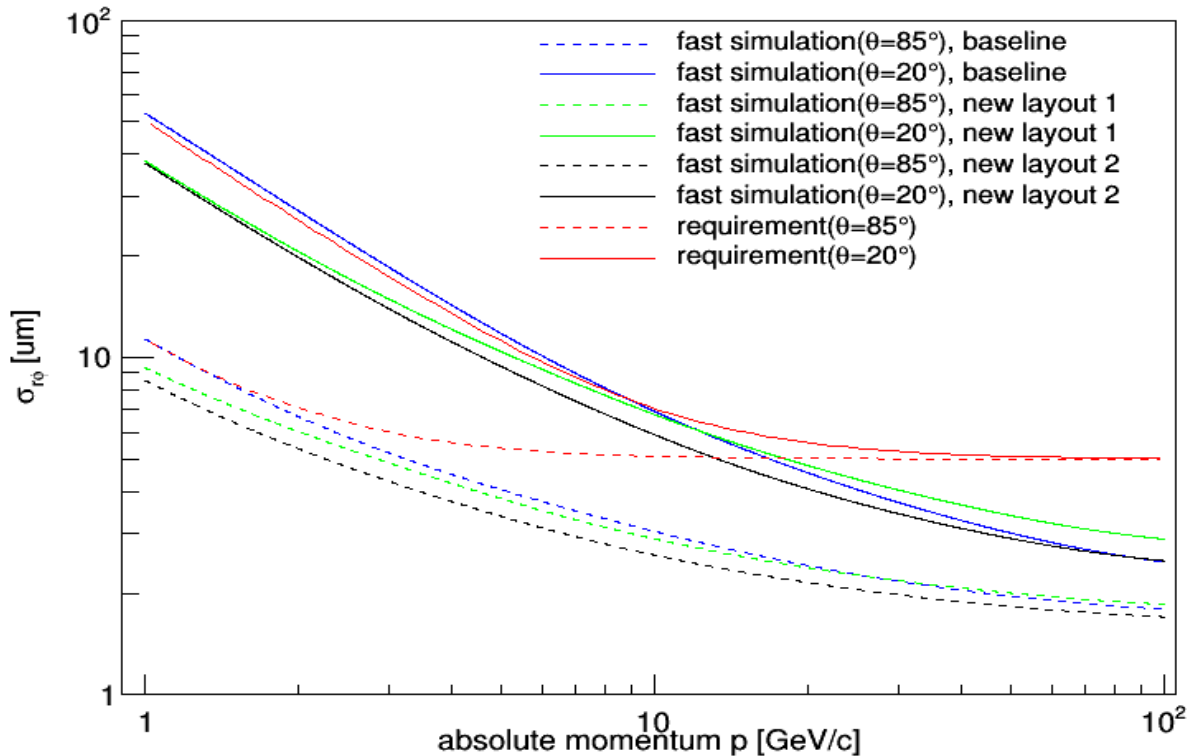
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	R(mm)	Z (mm)	$\sigma(\mu m)$ (layout1/layout2)	material
Layer1	16	62.5	4/2.8	0.05% X ₀
Layer2	24	62.5	4/4	0.05% X ₀
Layer3	32	125	4/4	0.05% X ₀
Layer4	40	125	4/4	0.05% X ₀
Layer5	50	125	4/4	0.05% X ₀
Layer6	60	125	4/4	0.05% X ₀

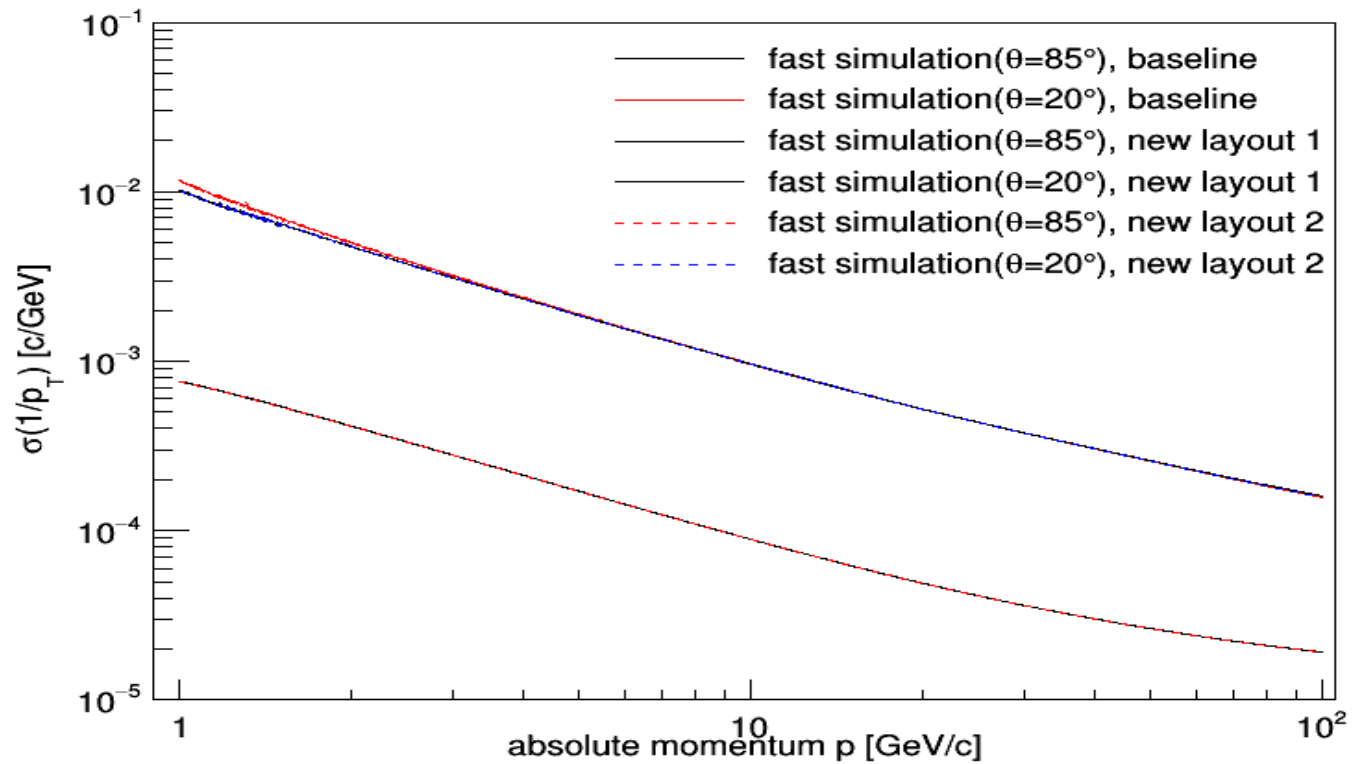
Impact parameter resolution: *fast simulation*



- better performance ($\sim 20\%$ improvement) for layout1 at low momentum, but poor performance at high momentum
- The performance of layout2 is better than baseline design
- both within the requirement

Material budget plays a major role at low momentum, while resolution plays a major role at high momentum.

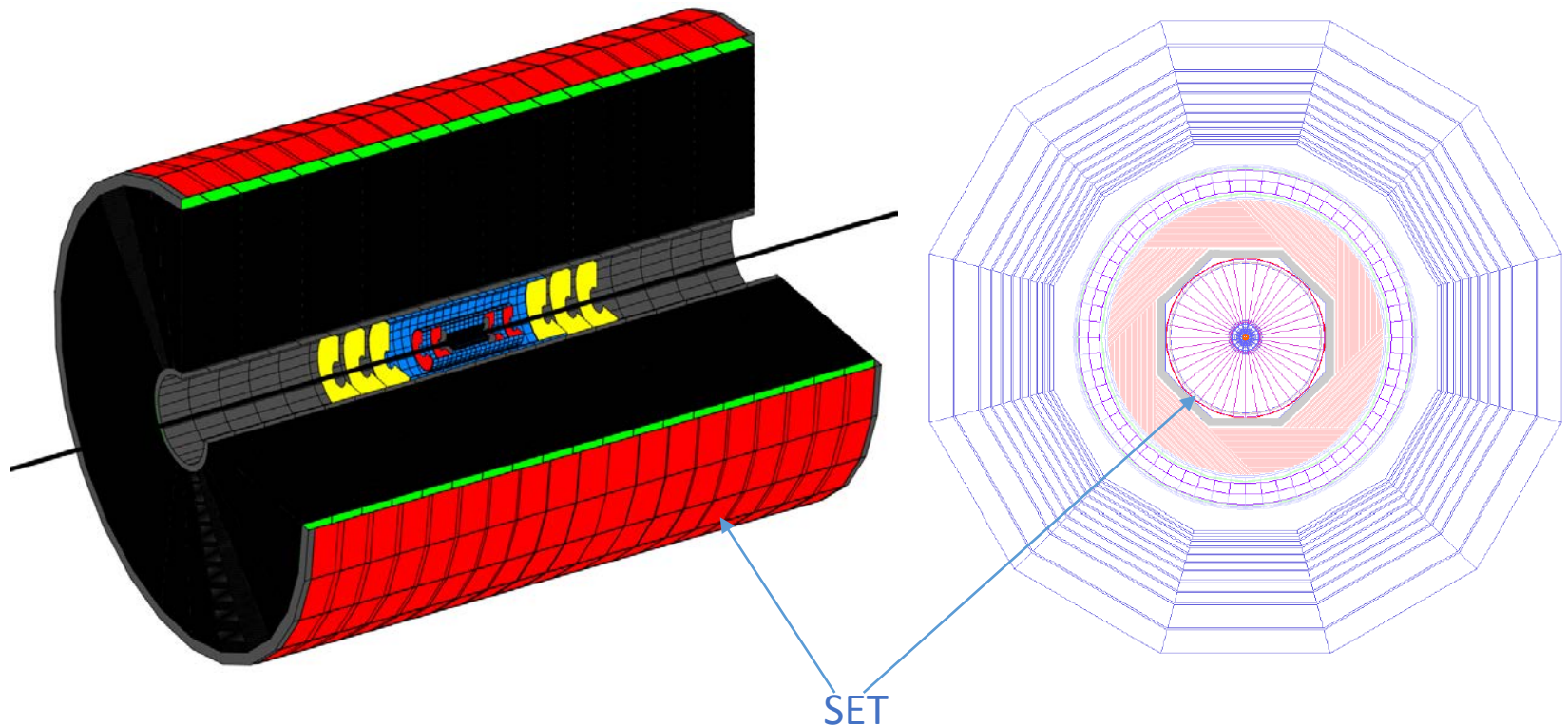
Momentum resolution : *fast simulation*



effect on p_T resolution is negligible

SET introduction

- Silicon External Tracker, providing precise hit points after the TPC
- Improving the overall tracking performance in the central region
- Extrapolating from the TPC to the calorimeter

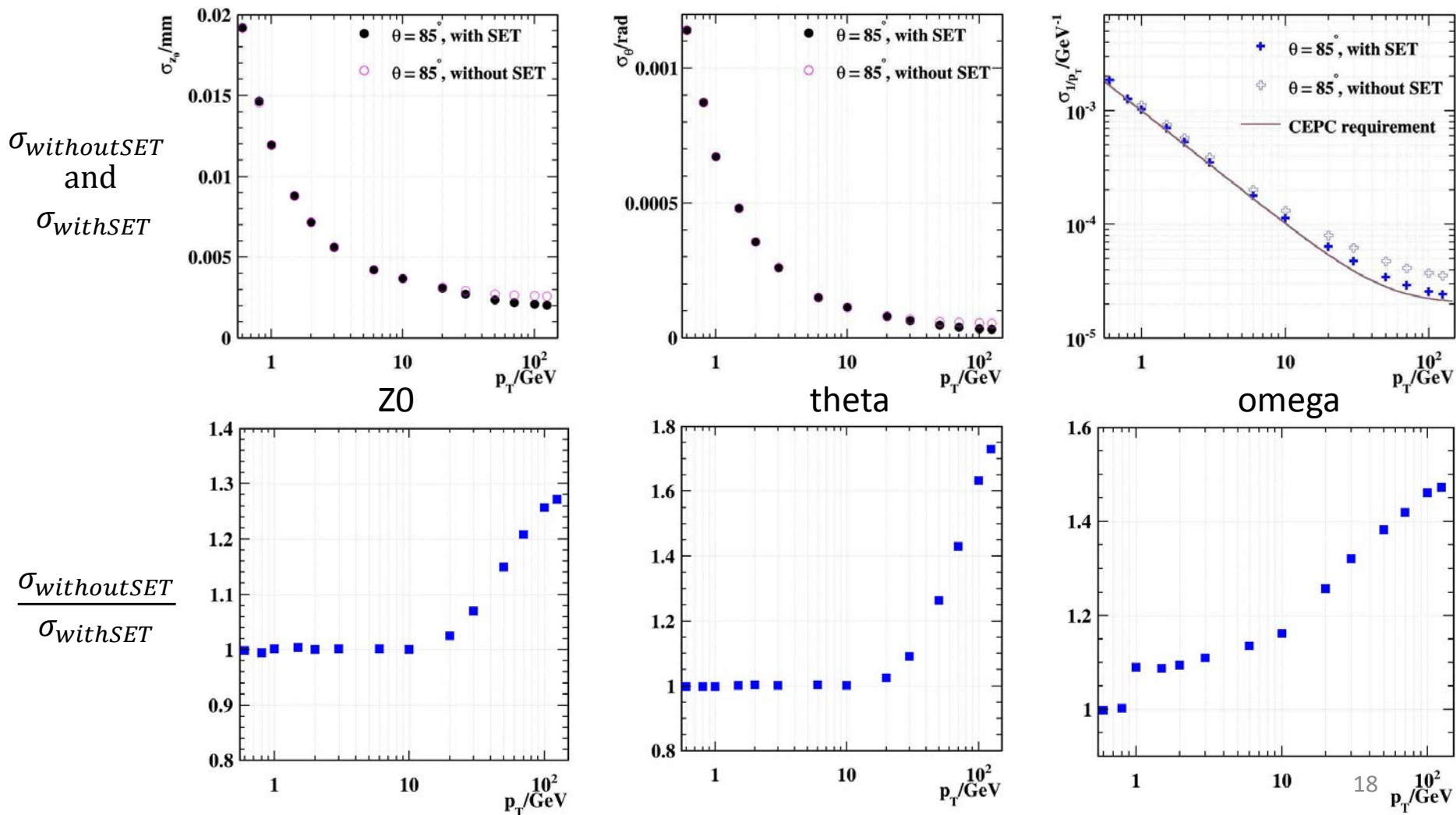


Effect of SET on track reconstruction

- SET has a high influence on the resolution of Z0, theta and omega

□ When Pt is high

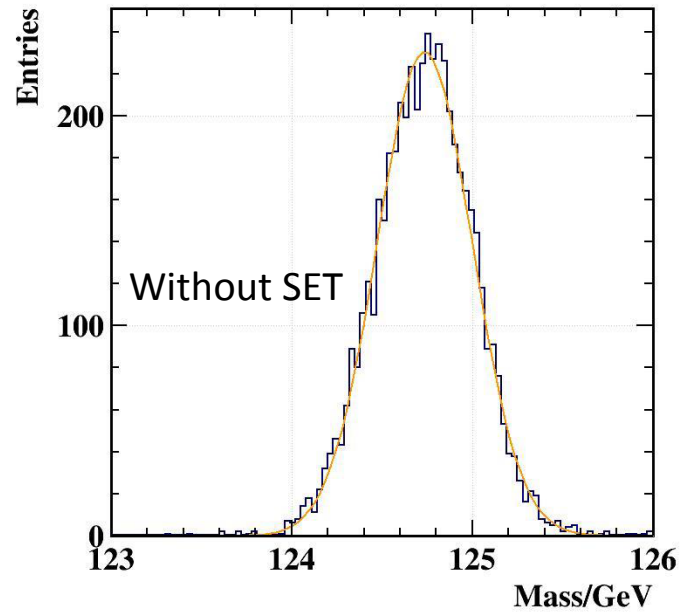
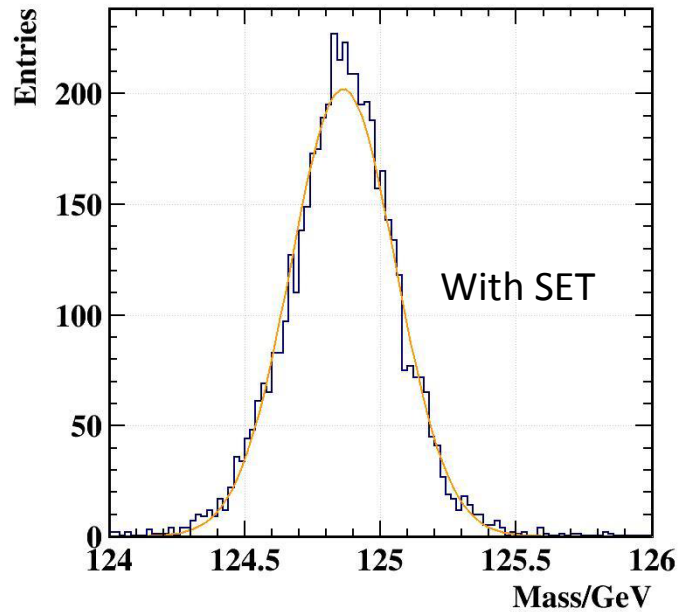
Made by Taifan.



Effect of SET on Higgs Mass reconstruction

- Higgs mass resolution in $H \rightarrow \mu^+ \mu^-$. Use MC information to find out true μ tracks
- High influence on Higgs Mass resolution

Made by Taifan.



Higgs mass resolution/MeV

	ZH recoil	nnH
withSET	213.4 \pm 4.7	193.7 \pm 2.2
w/o SET	297.5 \pm 6.3	263.5 \pm 2.7
	+39%	+36%

Thanks for your attention!

